

AMENDMENTS TO THE ABSTRACT:

Please amend the abstract as follows:

~~The present invention is a processing method of particulate dust in plasma, in which the~~
An apparatus for processing particulate dust in plasma is processed when a substrate ~~to be~~
~~processed~~ is arranged in ~~[[the]]~~ a high vacuum enclosure, plasma is generated in the high vacuum enclosure, and a reactive material is ~~appropriately~~ introduced into the high vacuum enclosure to perform processing of the substrate ~~to be processed~~. At least one collecting electrode is provided around the substrate ~~to be processed~~ in the high vacuum enclosure other than the electrode that generates plasma, and particulates generated in plasma are efficiently removed by applying a predetermined electric potential of a direct-current or an alternating current to the collecting electrode, and thus a deposition problem onto an inner wall of the vacuum enclosure and a deterioration problem of processing accuracy and a film quality associated with flowing of the particulates onto the substrate are solved.

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